



เอกสารอ้างอิง

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ประวัติผู้เขียน

นายอนุพงษ์ สรงประภา เกิดเมื่อวันที่ 13 พฤษภาคม พ.ศ.2501 ณ กรุงเทพมหานคร สำเร็จปริญญาตรี สาขาฟิลิกส์ จากคณะวิทยาศาสตร์ มหาวิทยาลัยมหิดล เมื่อปี พ.ศ. 2525 และได้เข้าศึกษาต่อในระดับปริญญาโทในสาขาวัฒน์พัฒนาบัณฑิต ณ คณะวิทยาศาสตร์ จุฬาลงกรณ์มหาวิทยาลัย



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